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Amendment of the claims under Article 19(1) (Rule 46)

International Application No. : PCT/JP03/13560
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Applicant's or Agent's File reference : FP0249PC-JS

Dear sir

The Applicant, who received the International Search Report relating to the above identified International Application transmitted on 02. 03. 2004, hereby files amendment under Article 19(1) as in the attached sheets.

The Claims 1 is amended.

The Claims 2 - 9 are unchanged.

The Applicant also files as attached herewith a brief statement explaining the amendment and indicating any impact that amendment therein might have on the description and drawings.

Very truly yours,


Seiji Kojima

Attachment :

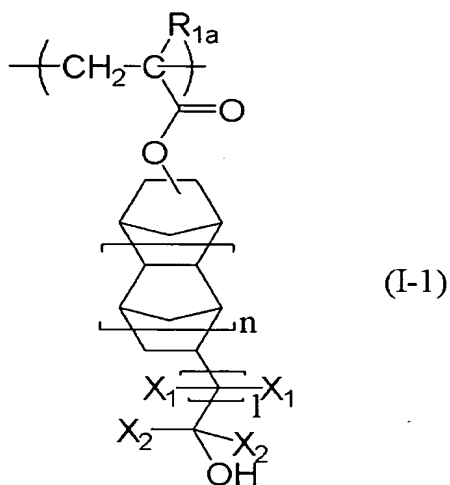
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| (1) Amendment under Article 19(1) | 1 sheet |
| (2) Brief Statement | 1 sheet |

CLAIMS

1. (Amended) A radiation-sensitive resin composition comprising:

(A) a resin which comprises a recurring unit (1-1) shown by the following

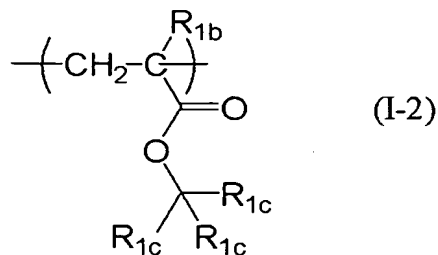
5 formula (I-1):



wherein R_{1a} represents a hydrogen atom, a methyl group, a hydroxyalkyl group having 1-4 carbon atoms, or a perfluoroalkyl group having 1-4 carbon atoms, X₁ represent a hydrogen atom, a fluorine atom, an alkyl group having 1-4 carbon atoms, or a fluoroalkyl group having 1-4 carbon atoms, X₂ represent a fluorine atom or a fluoroalkyl group having 1-4 carbon atoms, l is an integer of 0-5, and n is an integer of 0-2, the resin being insoluble or scarcely soluble in alkali, but becoming alkali soluble by the action of an acid, and

(B) a photoacid generator.

2. The radiation-sensitive resin composition according to claim 1, wherein the resin further comprises a recurring unit (1-2) shown by the following formula (I-2):



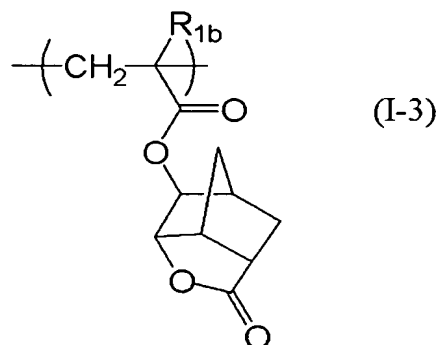
wherein R_{1b} represents a hydrogen atom or a methyl group, R_{1c} individually represents a monovalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, or a linear or branched alkyl group having 1-4 carbon atoms, provided that (1) at least one of the R_{1c} groups is a monovalent alicyclic hydrocarbon group having 4-20 carbon atoms, or (2) any two of the R_{1c} groups form, in combination and together with the carbon atom with which these groups bond, a divalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, with the other R_{1c} group being a monovalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, or a linear or branched alkyl group having 1-4 carbon atoms.

3. The radiation sensitive resin composition according to claim 2, wherein the group $-\text{C}(\text{R}_{1c})_3$ in the formula (I-2) is a 1-alkyl-1-cycloalkyl group, 2-alkyl-2-adamantyl group, (1-alkyl-1-adamantyl)alkyl group, or (1-alkyl-1-norbornyl)alkyl group.

4. The radiation-sensitive resin composition according to claim 1, wherein the resin does not contain a lactone ring.

5. The radiation-sensitive resin composition according to claim 4, wherein the content of the recurring unit (1-1) in the resin is 40-90 mol% in 100 mol% of the total recurring units forming the resin.

6. The radiation-sensitive resin composition according to claim 1, wherein the resin further comprises a recurring unit (I-3) shown by the following formula (I-3):



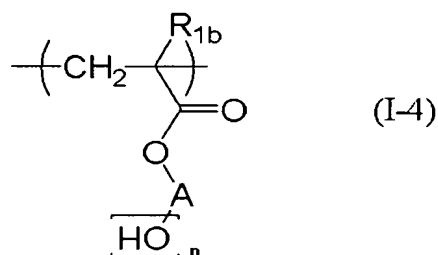
wherein R_{1b} represents a hydrogen atom or a methyl group.

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7. The radiation-sensitive resin composition according to claim 6, wherein the content of the recurring unit (I-1) in the resin is 5-25 mol% in 100 mol% of the total recurring units forming the resin.

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8. The radiation-sensitive resin composition according to claim 1, wherein the resin further comprises a recurring unit (I-4) shown by the following formula (I-4):



wherein R_{1b} represents a hydrogen atom or a methyl group, A represents a linear or branched alkyl or alkylene group having 1-4 carbon atoms or a monovalent or divalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, and n is an

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integer of 0-2.

9. The radiation-sensitive resin composition according to claim 1, further comprising (C) an acid diffusion controller.

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